## Semiconductor physics: basics

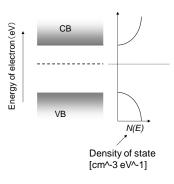
### Diagram of theories

Solid-state physics

Semiconductor (Device) physics

Semiconductor Device Design

#### **Band structure**

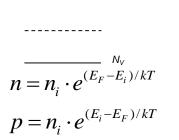


Boltzmann

Approximation

Fermi-Dirac distribution. Density of state and electron density

#### **Carrier concentration**



Thermal equilibrium condition

Energy → Potential

$$n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi)}$$

$$p = n_i \cdot e^{\frac{q}{kT}(\phi - \varphi)}$$

**Carrier and potential (Voltage)** 

$$p = n_i \cdot e^{\frac{q}{kT}(\phi - \varphi)}$$

#### **Drift – Diffusion Model**

$$J_n = -q \,\mu_n \, n \frac{d\varphi}{dx} + q D_n \, \frac{dn}{dx}$$

$$J_p = -q \,\mu_p \, p \frac{d\varphi}{dx} - q D_p \frac{dp}{dx}$$

Models in Other Fields

Boltzmann

Distribution

Ideal gas

### **Current continuity equation**

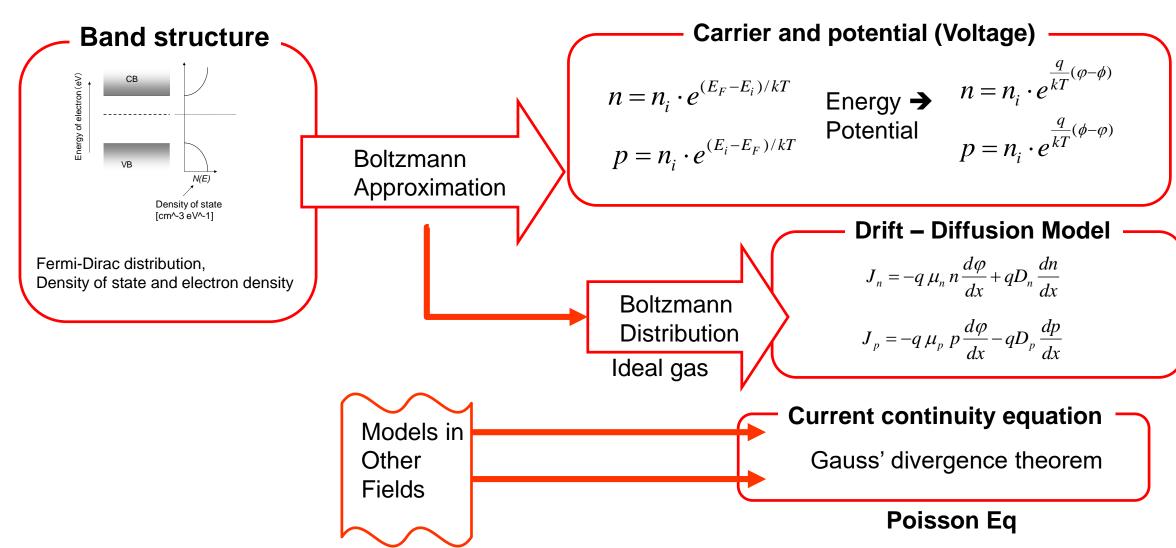
Gauss' divergence theorem

#### **Poisson Eq**

# Diagram of theories (today)

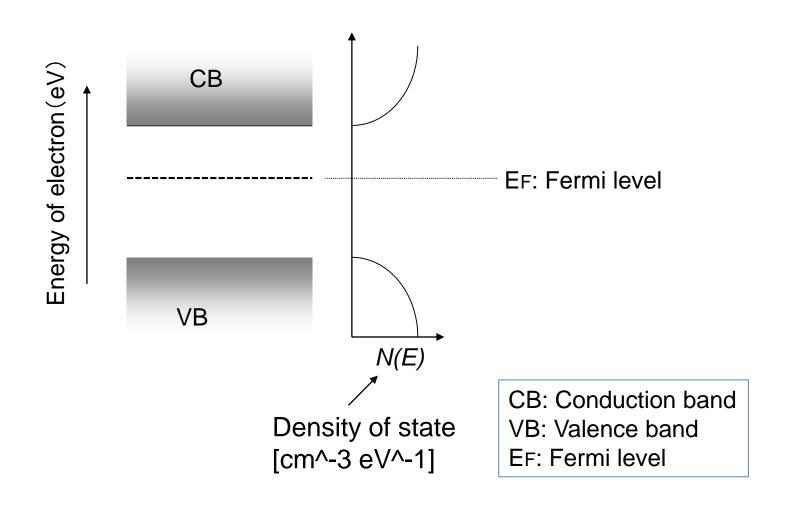
Solid-state physics Semiconductor (Device) physics

Semiconductor Device Design

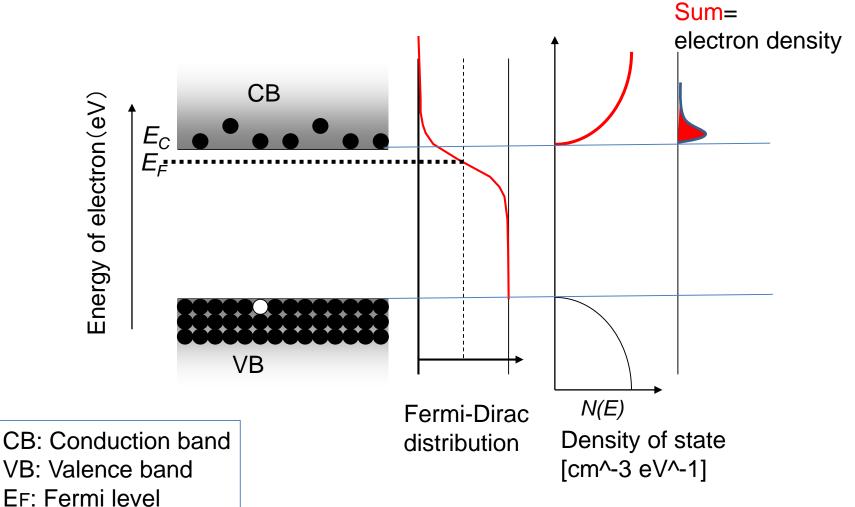


# Semiconductor physics basics

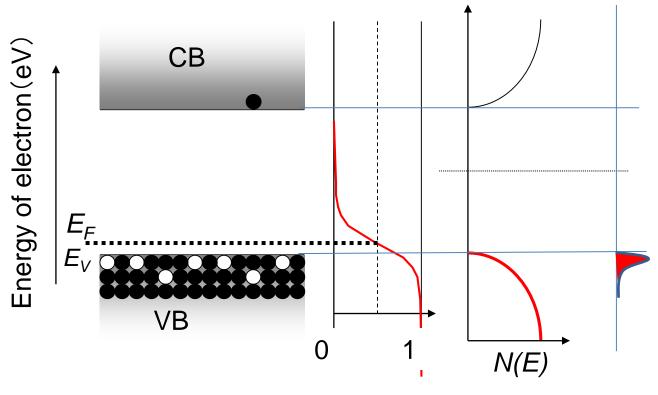
### Band gap of semiconductor



# Fermi-Dirac distribution, Density of state and electron density



# Fermi-Dirac distribution, Density of state and hole density



**CB**: Conduction band

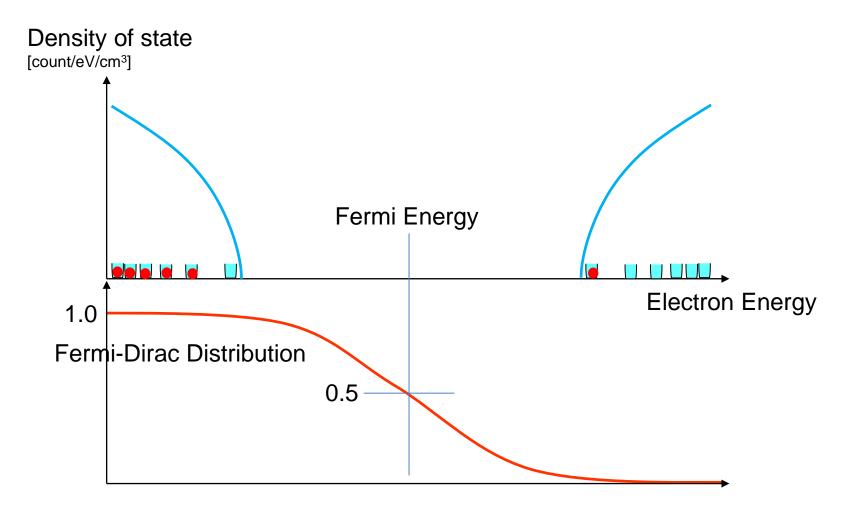
VB: Valence band

EF: Fermi level

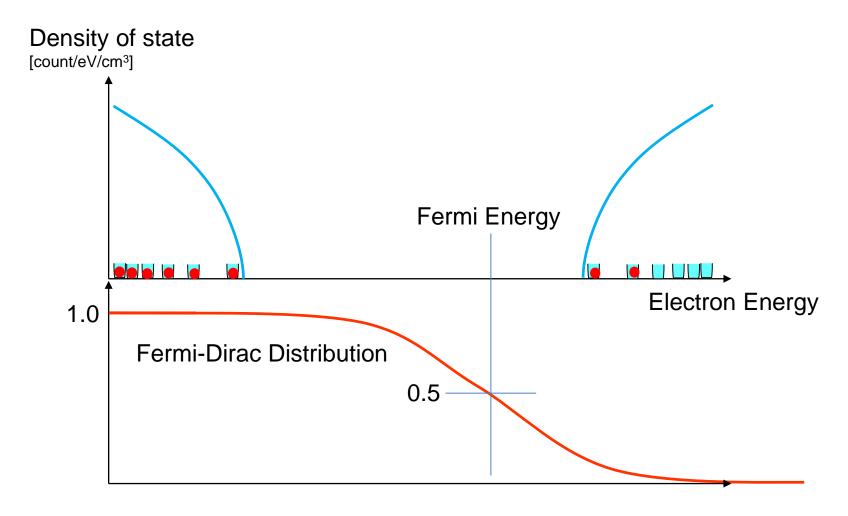
Fermi-Dirac distribution

Density of state [cm^-3 eV^-1]

# Remark: Density of state and Fermi energy



# Remark: Density of state and Fermi energy



### **Boltzmann Approximation**

Electron

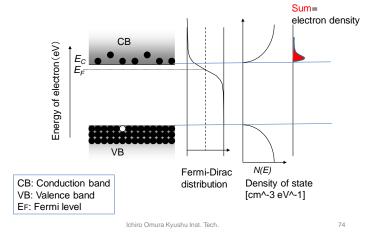
Fermi-Dirac distribution

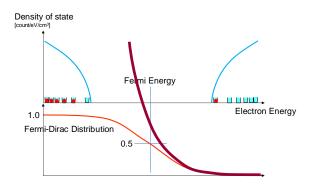
Density of state

$$n = \int_{E_c}^{\infty} \frac{1}{1 + e^{(E - E_F)/kT}} N(E) dE$$

$$\frac{1}{1 + e^{(E - E_F)/kT}} \approx e^{-(E - E_F)/kT}$$
>>1

$$n = \int_{E_F}^{\infty} e^{-(E - E_F)/kT} N(E) dE$$





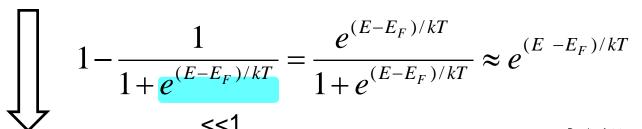
### **Boltzmann Approximation**

Hole

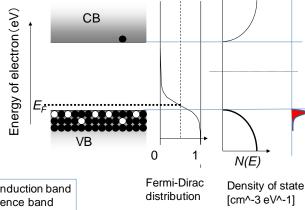
Fermi-Dirac distribution

Density of state

$$p = \int_{-\infty}^{E_V} \left\{ 1 - \frac{1}{1 + e^{(E - E_F)/kT}} \right\} N(E) dE$$

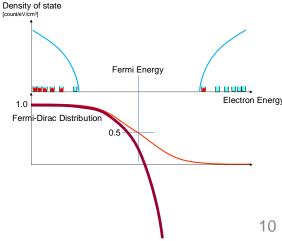


$$p = \int_{-\infty}^{E_F} e^{(E - E_F)/kT} N(E) dE$$



CB: Conduction band VB: Valence band

Er: Fermi level



# **Boltzmann Approximation** (Thermal Equilibrium)

$$n(E_F) = \int_{E_F}^{\infty} e^{-(E - E_F)/kT} N(E) dE$$

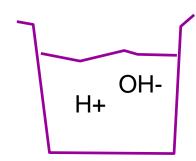
$$n(E_F) = \int_{E_F}^{\infty} e^{-(E - E_F)/kT} N(E) dE$$
 Hole  $p(E_F) = \int_{-\infty}^{E_F} e^{(E - E_F)/kT} N(E) dE$ 

$$\underline{p(E_F) \times n(E_F)} = \int_{E_F}^{\infty} e^{-(E - E_F)/kT} N(E) dE \times \int_{-\infty}^{E_F} e^{(E - E_F)/kT} N(E) dE$$

= Constant for any  $E_F$ 

Define intrinsic carrier density n<sub>i</sub> as,

$$n_i = \sqrt{p(E_F) \times n(E_F)} \longrightarrow p \cdot n = n_i^2$$



 $[H^+] \times [OH^-] = 1 \times 10^{-14} (mol/L)^2$ 

# Boltzmann Approximation (Thermal Equilibrium)

Ideal semiconductor crystal under thermal equilibrium

- → electric field =0
- → No space charge
- m = p is satisfied in the crystal and they are equal to  $\,n_i$

Intrinsic Fermi energy  $E_i$  is defined as Fermi energy satisfying,

$$n(E_i) = p(E_i) = n_i$$

$$n = n_i \cdot e^{(E_F - E_i)/kT}$$
  $p = n_i \cdot e^{(E_i - E_F)/kT}$ 

# Boltzmann Approximation to carrier density and potential

$$n = n_i \cdot e^{(E_F - E_i)/kT} \qquad p = n_i \cdot e^{(E_i - E_F)/kT}$$

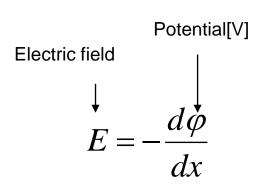
Potential 
$$\varphi = -\frac{E_i}{q}$$
 Fermi Potential  $\phi = -\frac{E_F}{q}$ 

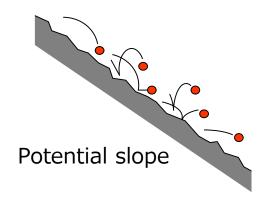
$$n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi)} \qquad p = n_i \cdot e^{\frac{q}{kT}(\phi - \varphi)}$$

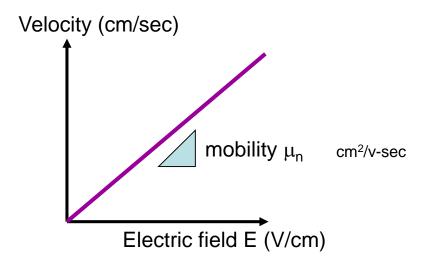
Good bye "Band theory", "electron energy", Density of state, Fermi-Dirac distribution!!

### **Drift velocity**

Velocity of electron 
$$v_n = -\mu_n \cdot E$$
 Velocity of hole 
$$v_p = \mu_p \cdot E$$





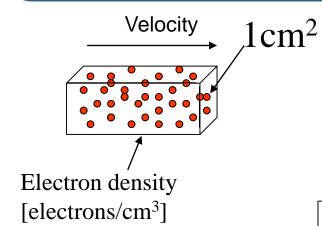


Flux: count/cm<sup>2\*</sup>sec

### Drift current density

**Drift current** = Electron charge X Drift carrier flux

Drift carrier flux [carriers/cm<sup>2</sup>/sec] = Carrier density [carriers/cm<sup>3</sup>] X <u>velocity</u>[cm/sec]



Electron drift current density[A/cm<sup>2</sup>]

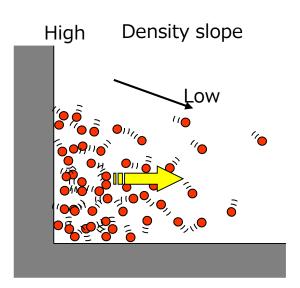
$$J_n = -qv_n n \qquad \qquad J_n = q \mu_n n E$$

Hole drift current density[A/cm<sup>2</sup>]

$$J_p = q v_p p \qquad \longrightarrow \qquad J_p = q \mu_p p E$$

## Diffusion current density

**Diffusion current**: Current by carrier diffusion with density difference



Electron diffusion flux  $=-D_n \frac{dn}{dx}$ 

Hole diffusion flux  $=-D_p \frac{dp}{dx}$ 

Electron diffusion current density

$$J_n = qD_n \frac{dn}{dx}$$

Hole diffusion current density

$$J_p = -qD_p \frac{dp}{dx}$$

# Drift-diffusion model = Current equation

#### **Electron and hole current density (Drift + diffusion)**

$$J_n = -q \,\mu_n \, n \frac{d\varphi}{dx} + q D_n \, \frac{dn}{dx}$$

$$J_{p} = -q \,\mu_{p} \, p \, \frac{d\varphi}{dx} - q D_{p} \, \frac{dp}{dx}$$

### Einstein relationship

$$\frac{D_n}{\mu_n} = \frac{kT}{q}, \quad \frac{D_p}{\mu_p} = \frac{kT}{q}$$

### Current in semiconductor

#### **Electron and hole current density (Drift + diffusion)**

$$J_n = -q \,\mu_n \, n \frac{d\varphi}{dx} + q D_n \frac{dn}{dx} \qquad J_p = -q \,\mu_p \, p \frac{d\varphi}{dx} - q D_p \frac{dp}{dx}$$

#### Total current in semiconductor

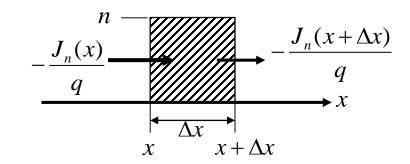
$$J = J_n + J_p + J_{disp}$$

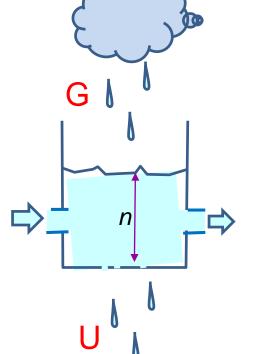
$$J_{disp} = \frac{d\varepsilon E}{dt}$$

Displacement current

### Current continuity equation

Continuity equations for electron current and hole current





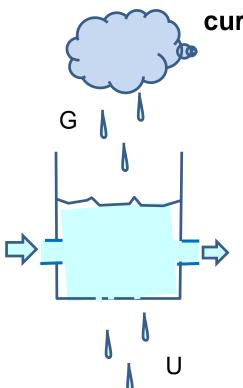
$$\frac{dn}{dt}\Delta x = -\frac{J_n(x)}{q} + \frac{J_n(x + \Delta x)}{q} + G_n \cdot \Delta x - U_n \cdot \Delta x$$

Gauss' Theorem

Gp, Gn: carrier generation rate [Carriers/cm³/sec] Un, Up: carrier recombination rate [Carriers/cm³/sec]

### Current continuity equation

Continuity equations for electron current and hole current



$$\frac{dn}{dt}\Delta x = -\frac{J_n(x)}{q} + \frac{J_n(x + \Delta x)}{q} + G_n \cdot \Delta x - U_n \cdot \Delta x$$

$$\downarrow \Delta t \Rightarrow \text{zero}$$

$$\frac{dn}{dt} = \frac{1}{q} \frac{dJ_n}{dx} + G_n - U_n$$

$$\frac{dp}{dt} = -\frac{1}{q} \frac{dJ_p}{dx} + G_p - U_p$$

Gp, Gn: carrier generation rate [Carriers/cm³/sec] Un, Up: carrier recombination rate [Carriers/cm³/sec]

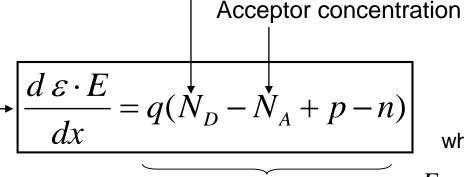
### Poisson eq. and Donor / acceptor

Donor concentration

#### **Poisson equation:**

Equation to obtain electric field

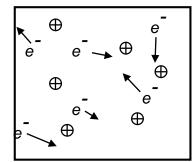
$$\frac{d\,\varepsilon \cdot E}{dx} = \rho$$
Poisson eq.



Charge density[C/cm<sup>3</sup>]

where 
$$E = -\frac{d\varphi}{dx}$$

Free electron and fixed positive charge (Donor)  $(N_D)$ 



Free hole and fixed negative charge (Acceptor)  $(N_A)$ 

.....under equilibrium condition

### Quasi Fermi Potentials

**Expand the Fermi Potential to Non-thermal-equilibrium conditions** 

Electron quasi Fermi potential 
$$\phi_n$$
  $n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi_n)}$ 

Hole quasi Fermi potential 
$$\phi_p$$
  $p = n_i \cdot e^{\frac{q}{kT}(\phi_p - \varphi)}$ 

Under thermal equilibrium condition  $\phi_n = \phi_n$ 

Current equation for electron and hole can be expressed by quasi Fermi potentials (Problem -> prove this, use "Einstein relationship", see next page)

$$J_n = -q \,\mu_n \, n \frac{d\phi_n}{dx} \qquad \qquad J_p = -q \,\mu_p \, p \frac{d\phi_p}{dx}$$

### Problem

$$n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi_n)} \qquad p = n_i \cdot e^{\frac{q}{kT}(\phi_p - \varphi)}$$

$$J_n = -q \,\mu_n \, n \frac{d\varphi}{dx} + q D_n \frac{dn}{dx} \qquad J_p = -q \,\mu_p \, p \frac{d\varphi}{dx} - q D_p \frac{dp}{dx}$$

Einstein relationship  $\frac{D_n}{\mu_n} = \frac{kT}{q}, \quad \frac{D_p}{\mu_p} = \frac{kT}{q}$ 



Prove following eq.

$$J_n = -q \,\mu_n \, n \frac{d\phi_n}{dx} \qquad J_p = -q \,\mu_p \, p \frac{d\phi_p}{dx}$$

### Summary of basic equations

#### Equations used in power semiconductor device design

#### **Current equations**

$$J_n = -q \,\mu_n \, n \frac{d\varphi}{dx} + q D_n \, \frac{dn}{dx}$$

$$J_{p} = -q \mu_{p} p \frac{d\varphi}{dx} - qD_{p} \frac{dp}{dx}$$

#### Current continuity equations

$$\frac{dn}{dt} = \frac{1}{q} \frac{dJ_n}{dx} + G_n - U_n$$

$$\left| \frac{dp}{dt} = -\frac{1}{q} \frac{dJ_p}{dx} + G_p - U_p \right|$$

#### Poisson equation

$$\frac{d \varepsilon \cdot E}{dx} = q(N_D - N_A + p - n) \quad \text{where} E = -\frac{d\varphi}{dx}$$

where
$$E = -\frac{d\varphi}{dx}$$

No band theory, no electron energy=>For device design use

Problem: Where is bandgap parameter in the equations??

### Related equations

#### Einstein relationship

$$\left| \frac{D_n}{\mu_n} = \frac{kT}{q}, \quad \frac{D_p}{\mu_p} = \frac{kT}{q} \right|$$

Displacement current and total current

$$J_{disp} = \frac{d\varepsilon E}{dt}$$

$$J = J_n + J_p + J_{disp}$$

Carrier density and current density by quasi Fermi potential

$$n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi_n)}$$

$$J_n = -q \,\mu_n \, n \frac{d\phi_n}{dx}$$

$$p = n_i \cdot e^{\frac{q}{kT}(\phi_p - \varphi)}$$

$$J_p = -q \,\mu_p \, p \, \frac{d\phi_p}{dx}$$

### Potentials at Ohmic contact

#### **Metal contact (Ohmic)**

Rem.

Under thermal equilibrium condition,

$$\frac{d \varepsilon \cdot E}{dx} = q(N_D - N_A + p - n) = 0$$



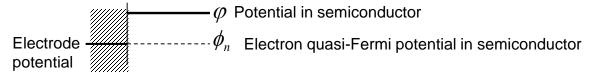
$$N_D - N_A + p - n = 0$$
$$p \cdot n = n_i^2$$

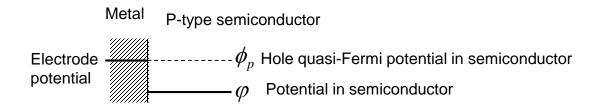
Need to solve equations for accurate hole, electron concentration and built-in potentials

#### **Built-in potential**

$$N_D \approx n = n_i e^{\frac{q}{kT}(\varphi - \phi_n)}$$
  $V_{built-in} = \frac{kT}{q} \log \frac{N_D}{n_i}$   $V_{A} \approx p = n_i e^{\frac{q}{kT}(\phi_p - \varphi)}$   $V_{built-in} = -\frac{kT}{q} \log \frac{N_A}{n_i}$ 

Metal N-type semiconductor



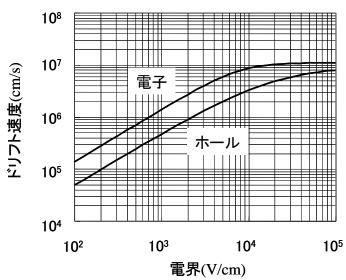


# Electron and hole mobility for silicon

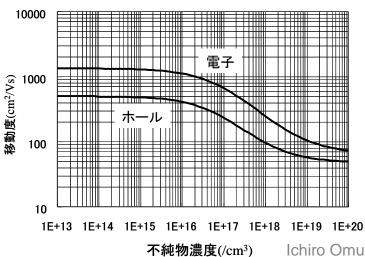
#### Electron and hole mobility for silicon

### 1500 1500 (\*\*) 1000 (\*\*) 1000 ボール (\*\*) 1000 10 10<sup>2</sup> 10<sup>3</sup> 10<sup>4</sup> 10<sup>5</sup> 電界(V/cm)

#### Electron and hole velocity for silicon



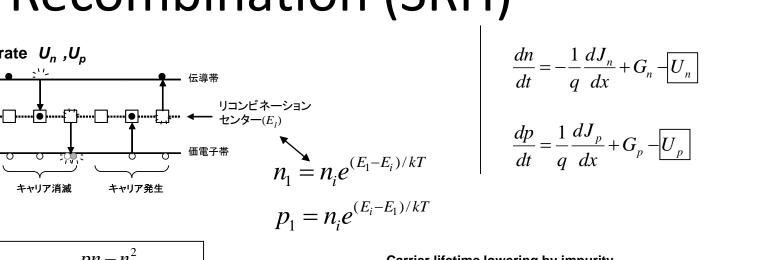
#### **Mobilities as functions of impurity concentration**



## Recombination (SRH)



SRH type recombination



$$\frac{dn}{dt} = -\frac{1}{q} \frac{dJ_n}{dx} + G_n - U_n$$

$$\frac{dp}{dt} = \frac{1}{q} \frac{dJ_p}{dx} + G_p - \overline{U_p}$$

#### Electron and hole lifetime

$$U_n^{SRH} = U_p^{SRH} = \frac{pn - n_i^2}{\tau_p(n + n_1) + \tau_n(p + p_1)}$$

#### In N-type semiconductor $(n=N_D>>p)$

$$U_n^{SRH} = U_p^{SRH} = \frac{p - p_{n0}}{\tau_p}$$

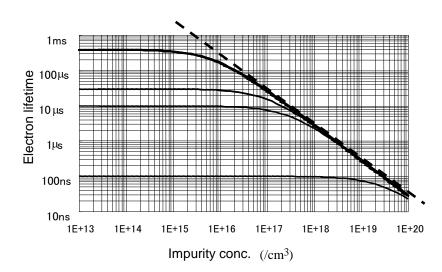
#### In P-type semiconductor $(p=N_A>>n)$

$$U_n^{SRH} = U_p^{SRH} \cong \boxed{\frac{n - n_{p0}}{\tau_n}}$$

 $p_{n0}$ : hole density in N-type semiconductor

 $n_{p0}$ : electron density in P-type semiconductor

#### Carrier lifetime lowering by impurity



# Impact ionization

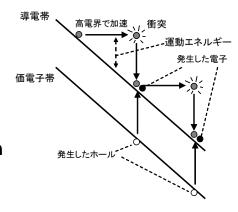
#### Carrier generation / impact ionization

**Ionization rate** 

$$egin{aligned} lpha_n(E) &= A_n e^{-b_n/|E|} \ lpha_p(E) &= A_p e^{-b_p/|E|} \end{aligned}$$

Carrier generation rate by impact ionization

$$G_n^{imp} = G_p^{imp} = \frac{1}{q} \left( \alpha_n |J_n| + \alpha_p |J_p| \right)$$



#### Example of parameters

$$A_n = 7.03 \times 10^5 [\text{cm}^{-1}]$$
  
 $A_p = 1.582 \times 10^6 [\text{cm}^{-1}]$   
 $b_n = 1.23 \times 10^6 [\text{V/cm}]$   
 $b_p = 2.036 \times 10^6 [\text{V/cm}]$ 

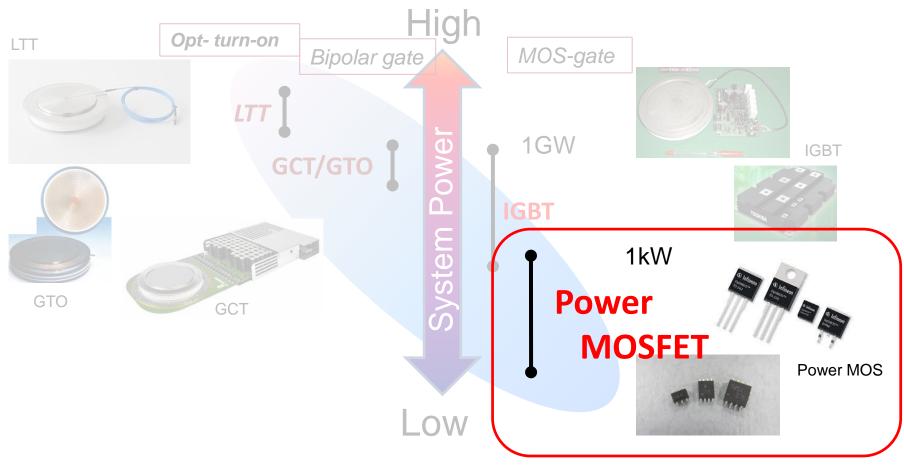
$$\frac{dn}{dt} = -\frac{1}{q} \frac{dJ_n}{dx} + \boxed{G_n} - U_n$$

$$\frac{dp}{dt} = \frac{1}{q} \frac{dJ_p}{dx} + \boxed{G_p} - U_p$$

**Ionization rate**: number of electron-hole pairs generated by moving electron or holes for 1cm

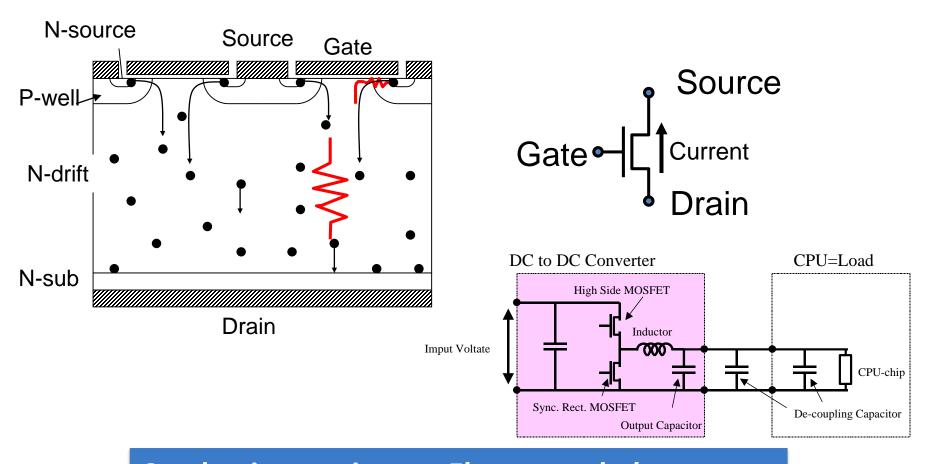
Carrier generation rate: number of electron-hole pairs generated in 1 cm3 for 1 sec.

### **Power MOSFET**



Photos: Infineon Toshiba ABB TMEIC

### **Power MOSFET**



Conduction carrier..... *Electron or hole*Switching control ...... *MOS-gate*Switching Freq. ...... *High* 

Ichiro Omura Kyushu Inst. Tech.

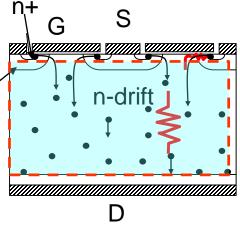
### **Function of N-drift layer**

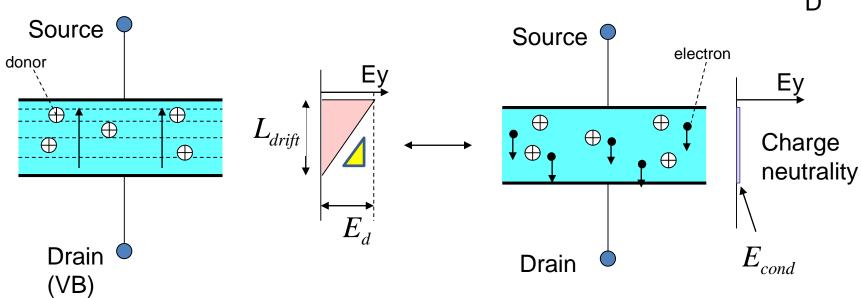
#### **Function of N-drift layer:**

- 1. Voltage blocking (higher breakdown voltage)
- 2. Current conduction (lower resistivity)

Voltage Blocking

Conduction





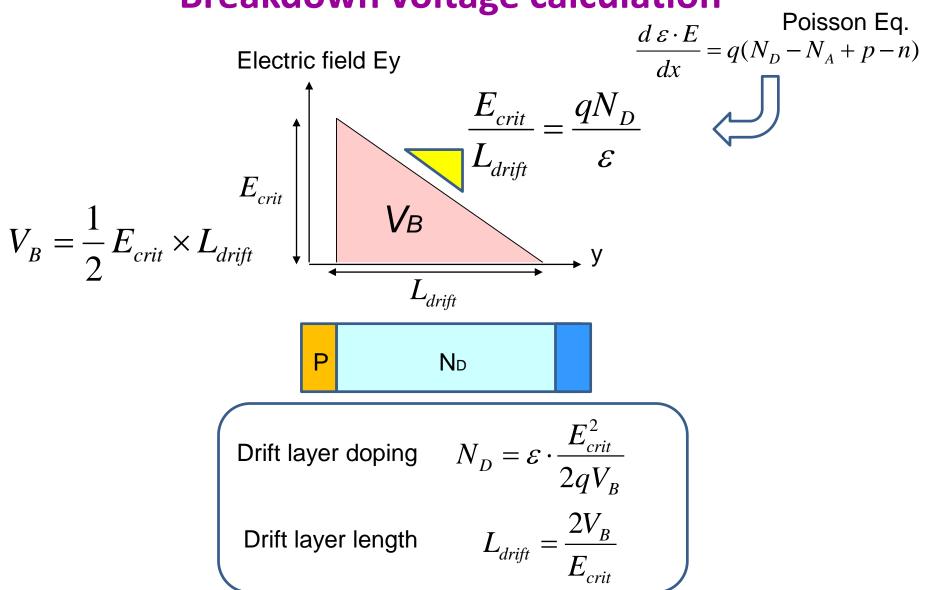
Blocking state (Poisson eq.)

$$qN_D = -\varepsilon \frac{dE_y}{dy} = \varepsilon \cdot \frac{E_d}{L_{drift}}$$

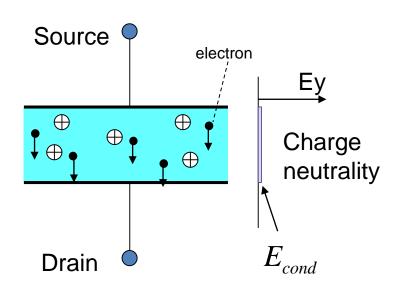
Conduction state (current eq.)

$$oxed{J_{n} = q\mu_{n}N_{D}E_{cond} = q\mu_{n}N_{D}rac{V_{cond}}{L_{drift}}}$$

### **Breakdown voltage calculation**



### **Conduction resistance calculation**



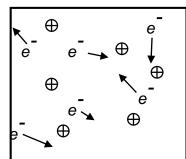
#### Conduction resistance

$$\begin{split} J_n &= q\mu_n N_D E_{cond} = q\mu_n N_D \frac{V_{cond}}{L_{drift}} \\ R_{on} A &= \frac{L_{drift}}{q\mu_n N_D} \quad \text{Resistance for unit area} \end{split}$$

$$\frac{d \varepsilon \cdot E}{dx} = q(N_D - N_A + p - n) \approx 0$$

$$\boxed{n \approx N_D}$$

Free electron and fixed positive charge (Donor)  $(N_D)$ 



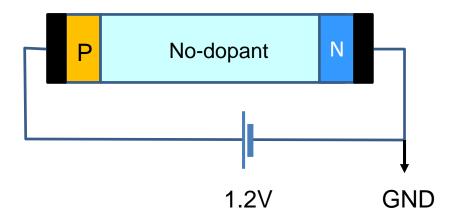
#### **Problem**

- 1.Calculate required drift length for breakdown voltage 1200V. (Ecrit=2.0E5 V/cm)
- 2. Calculate donor concentration for drift layer (q=1.6E-19 C,  $\epsilon$ =1.0e-12 [F/cm](silicon)
- 3. Calculate drift resistance (mobility of electron 1500 cm^2/V-s)
- 4. Calculate 1~3 for 600V, 1700V,

Problem: Draw potential distribution in PiN diode and electrode



Problem: Draw potential distribution in PiN diode, assume constant stored carrier n<sub>store</sub>



### Not to be used in the lecture

### **Boltzmann Approximation**

Electron

$$n = \int_{E_c}^{\infty} e^{-(E - E_F)/kT} N(E) dE$$

$$= e^{-(E_C - E_F)/kT} \int_{E_c}^{\infty} e^{-(E - E_C)/kT} N(E) dE$$

$$N_C \text{ Effective Density of State}$$

$$|n=N_C\cdot e^{-(E_C-E_F)/kT}|$$

### **Boltzmann Approximation**

Hole

Fermi-Dirac distribution

Density of state

$$p = \int_{-\infty}^{E_V} \left\{ 1 - \frac{1}{1 + e^{(E - E_F)/kT}} \right\} N(E) dE$$

$$1 - \frac{1}{1 + e^{(E - E_F)/kT}} \approx e^{(E - E_F)/kT}$$

$$p = N_V \cdot e^{-(E_F - E_V)/kT}$$

$$p = \int_{-\infty}^{E_V} \left\{ 1 - \frac{1}{1 + e^{(E - E_F)/kT}} \right\} N(E) dE$$

$$\cong \int_{-\infty}^{E_V} e^{(E - E_F)/kT} N(E) dE$$

$$= e^{(E_V - E_F)/kT} \int_{-\infty}^{E_V} e^{(E - E_V)/kT} N(E) dE$$
Effective Density of State  $N_V$ 

### Intrinsic carrier density, ni

Pure semiconductor without impurity = Intrinsic semiconductor

Charge neutrality under thermal equilibrium  $\rightarrow p = n = n_i$ 

$$n_i = N_C \cdot e^{-(E_C - E_i)/kT}$$
 Electron density  $n_i = N_V \cdot e^{-(E_i - E_V)/kT}$  Hole density

$$n_{i} = \sqrt{N_{C} \cdot N_{V}} e^{-(E_{C} - E_{V})/2kT}$$

$$= \sqrt{N_{C} \cdot N_{V}} e^{-E_{g}/2kT}$$

$$= \sqrt{N_{C} \cdot N_{V}} e^{-E_{g}/2kT}$$

$$= N_{V}$$

Problem: Calculate intrinsic Fermi level, Ei

## Intrinsic carrier density and potentials

$$n = N_C \cdot e^{-(E_C - E_F)/kT}$$

$$n_i = N_C \cdot e^{-(E_C - E_i)/kT}$$

$$n_i = N_C \cdot e^{-(E_C - E_i)/kT}$$

$$n = n_i \cdot e^{(E_F - E_i)/kT}$$

$$p = N_V \cdot e^{-(E_F - E_V)/kT}$$

$$n_i = N_V \cdot e^{-(E_i - E_V)/kT}$$

$$n_i = N_V \cdot e^{-(E_i - E_V)/kT}$$

$$p = n_i \cdot e^{(E_i - E_F)/kT}$$

Potential 
$$\varphi = -\frac{E_i}{q}$$
 Fermi Potential  $\phi = -\frac{E_F}{q}$ 

$$n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi)}$$

$$p = n_i \cdot e^{\frac{q}{kT}(\phi - \varphi)}$$

# Thermal equilibrium condition

Potential[V] 
$$\varphi = -\frac{E_i}{q}$$
 Fermi Potential[V]  $\phi = -\frac{E_F}{q}$ 

$$n = n_i \cdot e^{\frac{q}{kT}(\varphi - \phi)}$$
  $p = n_i \cdot e^{\frac{q}{kT}(\phi - \varphi)}$ 

$$p \cdot n = n_i^2$$

$$[H^+] \times [OH^-] = 1 \times 10^{-14} (mol/L)^2$$

## Boltzmann Approximation (Appdx)

Electron 
$$n = \int_{E_a}^{\infty} e^{-(E - E_F)/kT} N(E) dE$$

Hole 
$$p = \int_{-\infty}^{E_V} e^{(E-E_F)/kT} N(E) dE$$

$$pn = \int_{E_{-}}^{\infty} e^{-(E - E_F)/kT} N(E) dE \times \int_{-\infty}^{E_V} e^{(E - E_F)/kT} N(E) dE \qquad = \text{Constant for any } \mathbf{E_F}$$

Define intrinsic carrier density n<sub>i</sub> as,

$$n_i = \sqrt{\int_{E_c}^{\infty} e^{-(E - E_F)/kT} N(E) dE} \times \int_{-\infty}^{E_V} e^{(E - E_F)/kT} N(E) dE \qquad p \cdot n = n_i^2$$

 $E_i$  is defined so that following equation is satisfied (p=n=n<sub>i</sub> for pure crystal from Poisson Eq.).

$$n_i = \int_{E_c}^{\infty} e^{-(E - E_i)/kT} N(E) dE = \int_{-\infty}^{E_V} e^{(E - E_i)/kT} N(E) dE$$

$$n = n_i \cdot e^{(E_F - E_i)/kT} \qquad p = n_i \cdot e^{(E_i - E_F)/kT}$$